AMENDMENT TO THE CLAIMS

The following listing of claims will replace all prior versions and listings of claims in the application.

1. (Currently Amended) <u>A method Method</u> for manufacturing a diamond film using a pulsed microwave plasma, in which, in a vacuum chamber, a plasma of finite volume is formed near a substrate by subjecting a gas containing at least hydrogen and carbon to <u>a-periodic</u> pulsed <u>discharge</u>, <u>discharges</u>, <u>which has a forming a repeated</u> succession of <u>a low-power state states</u> and <u>a high-power state</u>, <u>states</u>, and having a peak absorbed power P_C, so as to obtain at least carbon-containing radicals in the plasma and to deposit the said carbon-containing radicals on the substrate in order to form a diamond film thereon; <u>and</u>

characterized in that the power is being injected into the volume of the plasma with a peak power density of at least 100 W/cm³ while maintaining the substrate to a substrate temperature of between 700 °C and 1000 °C.

- 2. (Currently Amended) Method <u>The method</u> according to Claim 1, in which a plasma having at least one of the following features is generated near the substrate:
- the pulsed discharge has a certain peak absorbed power P_C and the ratio of the peak
 power to the volume of the plasma is between 100 W/cm³ and 250 W/cm³,
 - the maximum temperature of the plasma is between 3500 K and 5000 K,
- the temperature of the plasma in a boundary region of the plasma located less than 1
 cm from the surface of the substrate is between 1500 K and 3000 K and
- the plasma contains hydrogen atoms having a maximum concentration in the plasma of between 1.7×10^{16} and 5×10^{17} cm⁻³.
- 3. (Currently Amended) Method The method according to Claim 1 or Claim 2, in which said gas contains carbon and hydrogen in a carbon/hydrogen molar ratio of between 1% and 12%.
- 4. (Currently Amended) Method The method according to Claim 1, in which said gas contains at least one hydro-carbon, and a plasma having a concentration of the carbon-containing radicals of between 2×10^{14} cm⁻³ and 1×10^{15} cm⁻³ is generated.

- 5. (Currently Amended) Method <u>The method</u> according to Claim 1, in which a pulsed discharge is produced, in which the ratio of the duration of the high-power state to the duration of the low-power state is between 1/9 and 1.
- 6. (Currently Amended) Method <u>The method</u> according to Claim 1, in which at least one of the following parameters is estimated:
 - a substrate temperature,
 - a temperature of the plasma,
- a temperature of the plasma in said boundary region, located less than 1 cm from the surface of the substrate,
 - a concentration of atomic hydrogen in the plasma,
 - a concentration of carbon-containing radicals in the plasma,
- a concentration of carbon-containing radicals in said boundary region close to the plasma,
 - a pressure of the plasma and
 - a power density of the plasma,

and the power emitted as a function of time is adapted according to at least one of these parameters.

- 7. (Currently Amended) Method The method according to Claim 1, in which the plasma is contained in a cavity with at least one of the following properties:
 - the pulsed discharge has a peak power of at least 5 kW at 2.45 GHz,
 - the pressure of the plasma is between 100 mbar and 350 mbar and
- the gas containing hydrogen and carbon is emitted with a ration of the flow rate to the volume of plasma of between 0.75 and 7.5 sccm/cm³.
- 8. (Currently Amended) Method The method according to Claim 1, in which the plasma is contained in a cavity with at least one of the following properties:
 - the pulsed discharge has a peak power of at least 10 kW at 915 MHz,
 - the pressure of the plasma is between 100 mbar and 350 mbar and
- the gas containing hydrogen and carbon is emitted with a ratio of the flow rate to the volume of the plasma of between 0.75 and 7.5 sccm/cm³.